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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/711,130	08/26/2004	Douglas D. Coolbaugh	BUR920040067US1 (17542)	5129	
45601 7	590 08/11/2005	. EXAMINER			
•	COTT, MURPHY & PRE	LE, DUN	LE, DUNG ANH		
400 GARDEN CITY PLAZA GARDEN CITY, NY 11530			ART UNIT	PAPER NUMBER	
			2818		
			DATE MAILED: 08/11/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

					X/			
		Applica	tion No.	Applicant(s)	•			
Office Action Summary		10/711,	130	COOLBAUGH ET	AL.			
		Examin	er	Art Unit				
		DUNG A		2818				
Period for	- The MAILING DATE of this commun r Reply	ication appears on ti	he cover sheet with	the correspondence ad	dress			
THE M - Extens after S - If the p - If NO - Failure Any re	DRTENED STATUTORY PERIOD FOR MAILING DATE OF THIS COMMUNITY Sions of time may be available under the provisions SIX (6) MONTHS from the mailing date of this commo period for reply specified above is less than thirty (3 period for reply is specified above, the maximum state to reply within the set or extended period for reply period for reply period for reply bely received by the Office later than three months and patent term adjustment. See 37 CFR 1.704(b).	ICATION. of 37 CFR 1.136(a). In no enunication. 0) days, a reply within the statutory period will apply and will, by statute, cause the apply and the statute of the sta	event, however, may a rep latutory minimum of thirty (will expire SIX (6) MONTF pplication to become ABAI	oly be timely filed (30) days will be considered timely HS from the mailing date of this condoned to the con				
Status								
1)	Responsive to communication(s) file	ed on			Ì			
*	This action is FINAL . 2b)⊠ This action is non-final.							
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Dispositio	on of Claims							
5)□ 6)⊠ 7)□	Claim(s) <u>1-20</u> is/are pending in the ala) Of the above claim(s) is/a Claim(s) is/are allowed. Claim(s) <u>1-20</u> is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restrict	re withdrawn from c						
Application	on Papers		•					
10)🖾 7	The specification is objected to by the first of the drawing(s) filed on 26 August 20 Applicant may not request that any objected to Replacement drawing sheet(s) including the oath or declaration is objected to	0.04 is/are: a) \boxtimes according and a control of the drawing (s) the correction is required.) be held in abeyanc uired if the drawing(s	e. See 37 CFR 1.85(a). i) is objected to. See 37 CF	FR 1.121(d).			
Priority u	nder 35 U.S.C. § 119							
a)[Acknowledgment is made of a claim All b) Some * c) None of: 1. Certified copies of the priority 2. Certified copies of the priority 3. Copies of the certified copies application from the Internation ee the attached detailed Office action	documents have be documents have be of the priority documental Bureau (PCT R	een received. een received in Apments have been re ule 17.2(a)).	plication No eceived in this National	Stage			
A440.= h	(0)							
2) Notice 3) Inform	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (Footbook of Disclosure Statement(s) (PTO-1449 or No(s)/Mail Date		Paper No(s)/	immary (PTO-413) /Mail Date ormal Patent Application (PTC	Dle 0-152)			

. DETAILED ACTION

Oath/Declaration

The oath/declaration filed on 8/26/2004 is acceptable.

Information Disclosure Statement

This office acknowledges of the following items from the Applicant:

Information Disclosure Statement (IDS) filed on 8/26/2004 and made of record. The references cited on the PTOL 1449 form have been considered.

Specification

The specification has been checked to the extent necessary to determine the presence of all possible minor errors. However, the applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

Claim Rejections

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See In re Goodman, 11 F.3d Art Unit: 2818

1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970); and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Set of Claims 1- 18 are rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over Set of claims 1-16 of a copending application s/n 10/605439. Although the conflicting claims are not identical, they are not patentably distinct from each other because it would have been obvious to one of ordinary skill in the art at the time of the invention was made to measuring the resistance of the at least one resistor to determine actual resistance of the resistor after silicidation; and adjusting the resistance of the resistor to achieve a desired resistance value by introducing the step of silicidation process comprises depositing a conductive metal and annealing to cause reaction of the conductive metal with the underlying

polysilicon layer to form the precision polysilicon resistor in order to define inventive method of fabricating a resistor on a semiconductor substrate.

Set of Claims 19-20 are rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over Set of claims 17-20 of a co-pending application s/n 10/605439. Although the conflicting claims are not identical, they are not patentably distinct from each other because it would have been obvious to one of ordinary skill in the art at the time of the invention was made to adjusting the resistance of the resistor to achieve a desired resistance value, said adjusting comprises a rapid thermal anneal step or ion implantation and a low temperature rapid thermal anneal step by introducing the step of performing silicide processing to form the precision polysilicon resistor including the step of performing silicide processing includes performing a silicide formation thermal anneal followed by a silicide conversion thermal anneal to activate the resistor polysilicon ion implant dopant or the step of performing silicide processing includes performing a silicide formation thermal anneal followed by a silicide conversion thermal anneal in order to define inventive method of fabricating a resistor on a semiconductor substrate.

When responding to the office action, Applicants' are advice to provide the examiner with the line numbers and page numbers in the application and/or references cited to assist the examiner to locate the appropriate paragraphs.

A shortened statutory period for response to this action is set to expire 3 (three) months and 0 (zero) day from the day of this letter. Failure to respond within the period for response will cause the application to become abandoned (see M.P.E.P 710.02(b)).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dung A. Le whose telephone number is (571) 272-1784. The examiner can normally be reached on Monday-Tuesday and Thursday 6:00am- 4:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on (571) 272-1787. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 872-9306 for regular communications and (703) 872-9306 for After Final communications.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

DUNG A. LE Derimary Examiner Art Unit 2818